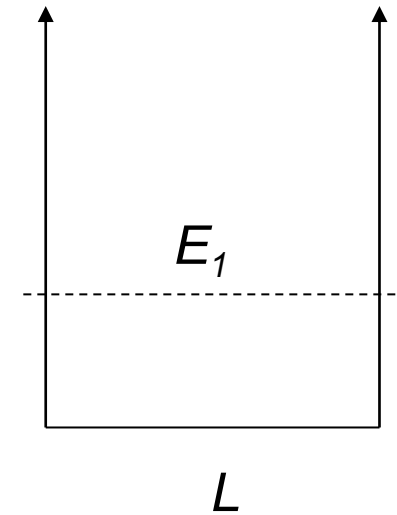


P08: Rectangular quantum well – mass dependence

Compare the **1st** allowed energy level for an electron trapped in an *infinite 1-dimensional rectangular* potential well of a length **L = 1 nm** , created in silicon Si.



$$m_e = 0.916 \cdot m_0$$

$$E_n = \frac{\hbar^2 \pi^2 n^2}{2m_e L^2} \quad n=1$$

$$E[\text{eV}] = \frac{E[\text{J}]}{q}$$

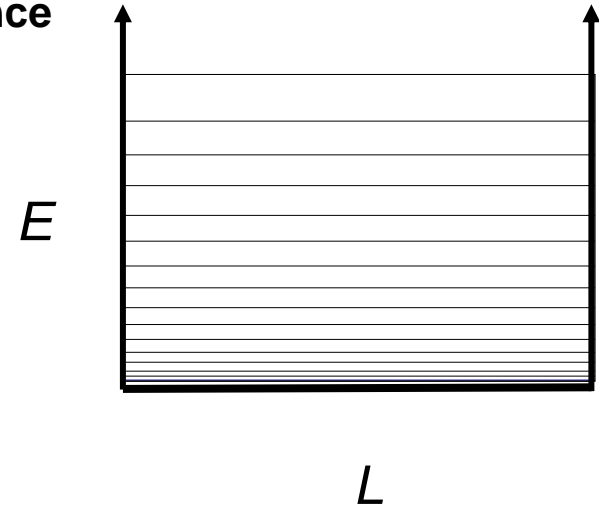
Material	m_e/m_0	E_n [eV]
Si	0.916	0.411

What happens to the energy levels when changing the potential well width?

$$\begin{aligned} h &= 6.626 \times 10^{-34} [\text{Js}] \\ \hbar &= \frac{h}{2\pi} = 1.055 \times 10^{-34} [\text{Js}] \\ m_0 &= 9.11 \times 10^{-31} [\text{kg}] \\ q &= 1.602 \times 10^{-19} [\text{C}] \\ k_B &= 1.381 \times 10^{-23} [\text{J/K}] \\ \epsilon_0 &= 8.854 \times 10^{-12} [\text{F/m}] \\ c &= 3 \times 10^8 [\text{m/s}] \end{aligned}$$

P08b: Rectangular quantum well – width dependence

Consider an Infinite 1-dimensional rectangular potential well created in silicon. Find the well's length **L**, such that the first **N=100** energy levels for electrons are located below an energy of **E = 1 eV**.



Solution:
$$E_N = \frac{\hbar^2 \pi^2}{2m_e} \frac{N^2}{L^2} < E$$

$$L > \frac{\hbar \pi N}{\sqrt{2m_e E}}$$

$$E[\text{eV}] = \frac{E[\text{J}]}{q}$$

Material	m_e/m_0	L [nm]
Si	0.916	64.1

$$h = 6.626 \times 10^{-34} [\text{Js}]$$

$$\hbar = \frac{h}{2\pi} = 1.055 \times 10^{-34} [\text{Js}]$$

$$m_0 = 9.11 \times 10^{-31} [\text{kg}]$$

$$q = 1.602 \times 10^{-19} [\text{C}]$$

$$k_B = 1.381 \times 10^{-23} [\text{J/K}]$$

$$\epsilon_0 = 8.854 \times 10^{-12} [\text{F/m}]$$

$$c = 3 \times 10^8 [\text{m/s}]$$